ABSTRACT

DEFECT INSPECTION APPARATUS, METHOD FOR INSPECTING DEFECT, AND METHOD FOR MANUFACTURING PHOTOMASK BLANK

A defect inspection apparatus has a defect detection unit 152 that acquires first defect information on a defect of a photomask blank MB as a substrate; and a comparative information acquisition unit 150 that acquires a result of comparison between predetermined defect information stored in a storage unit 155 and the first defect information.

FIG. 4